

2 / Prel. andt.

A

E. Willis
10-16-00

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Isao AMEMIYA

Appln. No.: Not yet assigned

Group Art Unit: Not yet assigned

Filed: June 30, 2000

Examiner: Not yet assigned

For: ELECTRON BEAM DRAWING MASK BLANK,
ELECTRON BEAM DRAWING MASK, AND METHOD
OF MANUFACTURING THE SAME

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Before prosecution on the merits, please amend the specification as follows:

IN THE CLAIMS:

Please amend the claims as follows:

A1 10. (Amended) An electron beam drawing mask blank as claimed in [any of the claims 1 to 9] claim 1, further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

A2 12. (Amended) An electron beam drawing mask blank as claimed in [any of the claims 1 to 11] claim 1, wherein said support member is made of a material composed substantially of the carbon element.

Claim 16, line 2, delete "or 15".

Claim 17, line 2, change "to 16", to --or 15--.

Claim 18, line 2, change "17" to --16--.

Claim 19, line 2, change "18" to --16--.